

Abstract

Method for fabricating a trench isolation structure

5 The invention provides a method for fabricating a trench
isolation structure, comprising the following steps:
forming a mask (3) on a substrate (1); forming at least
one trench (2) in the substrate (1) by means of the mask
(3); carrying out selective deposition of a first
10 insulation material (5) to at least partially fill the at
least one trench (2) in the substrate (1) with the
insulation material (5) in the presence of the mask (3);
and applying a second insulation material (6) over the
entire surface of the structure in order to fill the at
15 least one trench (2) in the substrate (1) at least up to
the top side of the mask (3).

Fig. 3